WHAT IS CLAIMED IS:

A solid-state imaging device having a first color picture cell array which contains picture cells having a photo-electric converting element for converting incident light to electric signals arranged two-dimensionally, and a second color picture cell array which contains picture cells having a photoelectric converting element for converting incident light to electric signals arranged two-dimensionally, placed in juxtaposition, on a substrate, wherein said substrate is provided with a common well being common to the first color picture cell array and the second color picture cell array.

- The solid-state imaging device according to claim 1, wherein a well-wiring and a well-contact are provided between the first color picture cell array and the second color picture cell array.
- The solid-state imaging device according to 20 3. claim 1, wherein an element isolation region is provided between the first color picture cell array and the second color picture cell array.
- The solid-state imaging device according to 25 claim 1, wherein a light-intercepting member is provided between the first color picture cell array and

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the second color picture cell array.

- 5. The solid-state imaging device according to claim 1, wherein the photo-electric converting element is a photodiode, the picture cell has plural transistors of an insulating gate type, the common well provides a first conductivity type semiconductor region for an anode or a cathode of the photodiode, and each first conductivity type well for the plural insulating gate type transistors.
- 6. The solid-state imaging device according to claim 1, wherein the photo-electric converting element is a photodiode, and the common well provides a first conductivity type semiconductor region for an anode or a cathode of the photodiode, and a well for formation of a charge transfer channel of CCD.
- 7. The solid-state imaging device according to claim 1, wherein a third color picture cell array is additionally provided so as to have said common well which array contains picture cells having a photoelectric converting element for converting incident light to electric signals arranged two-dimensionally.
 - 8. The solid-state imaging device according to claim 1, wherein the color picture cell arrays have

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respective common color filters on the photo-electric converting elements.

- 9. The solid-state imaging device according to claim 8, wherein the common color filter is a color filter of red, green, or blue.
- 10. The solid-state imaging device according to claim 1, which has a terminal for connection with a power source for supplying a voltage for generating a reference voltage for the common well from an outside of the solid-state imaging device.
- 11. A solid-state imaging device having a first color picture cell array which contains picture cells having a photo-electric converting element for converting incident light to electric signals arranged two-dimensionally, and a second color picture cell array which contains picture cells having a photo-electric converting element for converting incident light to electric signals arranged two-dimensionally, placed in juxtaposition on a substrate, wherein said solid-state imaging device has between the first color picture cell array and the second color picture cell array a well-contact and a well-wiring for applying a reference voltage to a common well common to the first color picture cell array and the second color picture

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cell array.

12. The solid-state imaging device according to claim 11, wherein the well-wiring is formed from a light-intercepting material to intercept the incident light upon the common well region between the first color picture cell array and the second color picture cell array.

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13. The solid-state imaging device according to claim 12, wherein the light-intercepting material is a metal mainly comprised of aluminum or copper.

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14. The solid-state imaging device according to claim 11, wherein an anti-reflection layer is formed on or above the well-wiring to prevent reflection of the incident light.

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15. The solid-state imaging device according to claim 14, wherein a main component of the anti-reflection layer is selected from the group constituting of titanium nitride, tantalum nitride, tungsten nitride and tungsten.

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16. The solid-state imaging device according to claim 11, wherein a plurality of the well-contacts are formed between the first color picture cell array and

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the second color picture cell array.

17. The solid-state imaging device according to claim 11, wherein the photo-electric converting element is a photodiode, the picture cell has plural transistors of an insulating gate type, the common well provides a first conductivity type semiconductor region for an anode or a cathode of the photodiode, and each first conductivity type well for the plural insulating gate type transistors.

- 18. The solid-state imaging device according to claim 11, wherein the photo-electric converting element is a photodiode, and the common well provides a first conductivity type semiconductor region for an anode or a cathode of the photodiode, and a well for formation of a charge transfer channel of CCD.
- 19. The solid-state imaging device according to
 20 claim 11, wherein a third color picture cell array is
 additionally provided which array contains picture
 cells having a photo-electric converting element for
 converting incident light to electric signals arranged
 two-dimensionally.

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20. The solid-state imaging device according to claim 11, wherein the color picture cell arrays have

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respective common color filters on the photo-electric converting elements.

A solid-state imaging device having a first 21. color picture cell array which contains picture cells having a photo-electric converting element for converting incident light to electric signals arranged two-dimensionally, a second and third picture cell arrays which respectively contain picture cells having a photo-electric converting element for converting incident light to electric signals arranged twodimensionally, and a\fourth color picture cell array which contains picture cells having a photo-electric converting element for converting incident light to electric signals arranged two-dimensionally, placed in juxtaposition on a substrate, wherein the first color picture cell array and the fourth color picture cell arkay are placed in a diagonal relation, and the second color picture cell array and the third color picture cell array are placed in another diagonal relation; and said solid-state imaging device has between the first color picture cell array and the second color picture cell array a well-contact and a well-wiring for applying a reference voltage to a common well common to at least the first color picture cell array and the second color picture cell array.

- 22. The solid-state imaging device according to claim 21, wherein the well-wiring is formed from a light-intercepting material to intercept the incident light upon the common well region between the first color picture cell array and the second color picture cell array.
- 23. The solid-state imaging device according to claim 22, wherein the light-intercepting material is a metal mainly comprised of aluminum or copper.
- 24. The solid-state imaging device according to claim 21, wherein an anti-reflection layer is formed on or above the well-wiring to prevent reflection of the incident light.
- 25. The solid-state imaging device according to claim 24, wherein a main component of the anti-reflection layer is selected from the group consisting of titanium nitride, tantalum nitride, tungsten nitride and tungsten.
- 26. The solid-state imaging device according to claim 21, wherein a plurality of the well-contacts are formed between the first color picture cell array and the second color picture cell array.

27. The solid-state imaging device according to claim 21, wherein the photo-electric converting element is a photodiode, the picture cell has plural transistors of an insulating gate type, the common well provides a first conductivity type semiconductor region for an anode or a cathode of the photodiode, and each first conductivity type well for the plural insulating gate type transistors.

28. The solid-state imaging device according to claim 21, wherein the photo-electric converting element is a photodiode, and the common well provides a first conductivity type semiconductor region for an anode or a cathode of the photodiode, and a well for formation of a charge transfer channel of CCD.

29. The solid-state imaging device according to claim 21, wherein a third color picture cell array is additionally provided which array contains picture cells having a photo-electric converting element for converting incident light to electric signals arranged two-dimensionally.

30. The solid-state imaging device according to claim 21, wherein the color picture cell arrays have respective common color filters on the photo-electric converting elements.

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- 31. The solid-state imaging device according to claim 21, wherein said solid-state imaging device has between the third color picture cell array and the fourth color picture cell array a well-contact and a well-wiring for applying a reference voltage to a common well common to at least the third color picture cell array and the fourth color picture cell array.
- 32. The solid-state imaging device according to claim 21, wherein the common well is common to all of the first to fourth picture cell arrays.
- 33. The solid-state imaging device according to claim 21, wherein the well-contact and the well-wiring for applying the reference voltage to the common well are not formed between the first color picture cell array and the third color picture cell array.
- 20 claim 21, wherein the first color picture cell array has a color filter of one color of red and blue, the second and the third color picture cell arrays have green filters respectively, and the fourth color picture cell array has a color filter of the other color of red and blue.
 - 35. An imaging device for imaging an object,

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comprising a solid-state imaging device set forth in claim 1, and a power source for supplying a voltage for generating a reference voltage for the well-wiring of the solid-state imaging device from an outside of the solid-state imaging device.

- 36. An imaging device for imaging an object, comprising a solid-state imaging device set forth in claim 1, and a focusing lens for focusing an image of an object on the color picture cell arrays.
- 37. An imaging device for imaging an object, comprising a solid-state imaging device set forth in claim 11, and a power source for supplying a voltage for generating a reference voltage for the well wiring of the solid-state imaging device from an outside of the solid-state imaging device.
- 20 comprising a solid-state imaging device set forth in claim 11, and a focusing lens for focusing an image of an object on the color picture cell arrays.
- 39. An imaging device for imaging an object,
 25 comprising a solid-state imaging device set forth in
 claim 21, and a power source for supplying a voltage
 for generating a reference voltage for the well wiring

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of the solid-state imaging device from an outside of the solid-state imaging device.

40. An imaging device for imaging an object, comprising a solid-state imaging device set forth in claim 21, and a focusing lens for focusing an image of an object on the color picture cell arrays.